

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	142	(etch\$4 or remov\$4) with plasma with radical\$1 with (oxygen or O2 or "O2" or "O.sub.2") with (fluorine or F or "F" or CF4 or "CF4" or "CF.sub.4" or "C F.sub.4" or CHF3 or "CHF3" or "CHF.sub.3" or "CH F.sub.3" or "C H F.sub.3" or "C HF.sub.3" or SF6 or "SF6" or "SF.sub.6" or "S F.sub.6" or NF3 or "NF3" or "NF.sub.3" or "N F.sub.3" or C2F6 or "C2F6" or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C4F8 or "C4F8" or "C.sub.4F.sub.8" or "C.sub.4 F.sub.8" or CH2F2 or "CH2F2" or "CH.sub.2F.sub.2" or "C H.sub.2 F.sub.2" or CH3F or "CH3F" or "CH.sub.3F" or "CH.sub.3 F" or "C H.sub.3 F" or C4F6 or "C4F6" or "C.sub.4F.sub.6" or "C.sub.4 F.sub.6")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:04
L2	426701	(silicon adj nitride\$1) or SiN or Si3N4 or "Si3N4" or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:07
L3	775	radical\$1 with ion\$1 with (ratio\$1 or relation\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:37
L4	7	1 with 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:37
L5	1	3 and 4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:38
L6	37881	(etch\$4 near2 stop\$4) or etch-stop\$4 or etched-stop\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:46

L7	2	1 with 6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:46
L8	6	1 same 6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:49
L9	20	1 same 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:50
L10	298698	nitride\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:03
L11	7	1 with 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:04
L12	1	11 not 4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:04
L13	19	1 same 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:05
L14	1	13 not 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:06

L15	6027	(copper\$1 or Cu or "Cu") near8 damascene\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:01
L16	6	1 and 15	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:07
L17	223	(prevent\$4 or minimiz\$4 or eliminat\$4 or reduc\$4 or stop\$4 or avoid\$4 or diminish\$4 or decreas\$4) near5 back near5 sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 09:31
L18	1570711	copper\$1 or Cu or "Cu"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:01
L19	12	17 with 18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:01
L20	251	plasma with radical\$1 with (oxygen or O2 or "O2" or "O.sub.2") with (fluorine or F or "F" or CF4 or "CF4" or "CF.sub.4" or "C F.sub.4" or CHF3 or "CHF3" or "CHF.sub.3" or "CH F.sub.3" or "C H F.sub.3" or "C HF.sub.3" or SF6 or "SF6" or "SF. sub.6" or "S F.sub.6" or NF3 or "NF3" or "NF.sub.3" or "N F.sub.3" or C2F6 or "C2F6" or "C.sub.2F.sub. 6" or "C.sub.2 F.sub.6" or C4F8 or "C4F8" or "C.sub.4F.sub.8" or "C. sub.4 F.sub.8" or CH2F2 or "CH2F2" or "CH.sub.2F.sub.2" or "C H.sub.2 F.sub.2" or CH3F or "CH3F" or "CH. sub.3F" or "CH.sub.3 F" or "C H. sub.3 F" or C4F6 or "C4F6" or "C. sub.4F.sub.6" or "C.sub.4 F.sub.6")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:03
L21	2	19 and 20	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:04

L22	690	(etch\$4 or remov\$4) same plasma same radical\$1 same (oxygen or O2 or "O2" or "O.sub.2") same (fluorine or F or "F" or CF4 or "CF4" or "CF.sub.4" or "C F.sub.4" or CHF3 or "CHF3" or "CHF.sub.3" or "CH F.sub.3" or "C H F.sub.3" or "C HF.sub.3" or SF6 or "SF6" or "SF.sub.6" or "S F.sub.6" or NF3 or "NF3" or "NF.sub.3" or "N F.sub.3" or C2F6 or "C2F6" or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C4F8 or "C4F8" or "C.sub.4F.sub.8" or "C.sub.4 F.sub.8" or CH2F2 or "CH2F2" or "CH.sub.2F.sub.2" or "C H.sub.2 F.sub.2" or CH3F or "CH3F" or "CH.sub.3F" or "CH.sub.3 F" or "C H.sub.3 F" or C4F6 or "C4F6" or "C.sub.4F.sub.6" or "C.sub.4 F.sub.6")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:05
L23	578570	2 or 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:07
L24	85	22 same 23	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:08
L25	3	24 and 3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:10
L26	6	24 and 15	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 10:36

S1	135	(etch\$4 or remov\$4) with plasma with radical\$1 with (oxygen or O2 or "O2" or "O.sub.2") with (fluorine or F or "F" or CF4 or "CF4" or "CF.sub.4" or "C F.sub.4" or CHF3 or "CHF3" or "CHF.sub.3" or "CH F.sub.3" or "C H F.sub.3" or "C HF.sub.3" or SF6 or "SF6" or "SF.sub.6" or "S F.sub.6" or NF3 or "NF3" or "NF.sub.3" or "N F.sub.3" or C2F6 or "C2F6" or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C4F8 or "C4F8" or "C.sub.4F.sub.8" or "C.sub.4 F.sub.8" or CH2F2 or "CH2F2" or "CH.sub.2F.sub.2" or "C H.sub.2 F.sub.2" or CH3F or "CH3F" or "CH.sub.3F" or "CH.sub.3 F" or "C H.sub.3 F" or C4F6 or "C4F6" or "C.sub.4F.sub.6" or "C.sub.4 F.sub.6")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:35
S2	417934	(silicon adj nitride\$1) or SiN or Si3N4 or "Si3N4" or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/06 08:35
S3	7	S1 with (S2 or nitride\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/25 11:23
S4	3	("6524950") or ("6579791") or ("6616855").PN.	US-PGPUB; USPAT	OR	OFF	2005/09/02 17:23